

**AMENDMENTS TO THE SPECIFICATION:**

**Please replace the paragraph beginning on page 5, line 1, with the following amended paragraph:**

Preferably, the mesh grid is formed of Invar®. Invar® (FeNi36) is a commercially available low thermal expansion alloy consisting of Fe, Ni, Cr, Mn, Si, C, P, S and Co.

**Please replace the paragraph beginning on page 5, line 19, with the following amended paragraph:**

Preferably, the mesh grid is formed of Invar® (FeNi36).

**Please replace the paragraph beginning on page 9, line 1, with the following amended paragraph:**

As shown in FIG. 10, a SiO<sub>2</sub> paste is printed on an Invar® (FeNi36) having a thickness of about 50 – 100 microns by squeezing the SiO<sub>2</sub> paste on the Invar® (FeNi36) and then is sintered at a temperature of about 530 °C

**Please replace the paragraph beginning on page 9, line 4, with the following amended paragraph:**

As shown in FIG. 11, an electron control hole 420 is formed in the Invar® (FeNi36) by photolithography. During the photolithography, a photoresist mask having a window corresponding to the electron control hole 420 can be used, and ferric chloride can be used as an etchant.

**Please replace the paragraph beginning on page 9, line 8, with the following amended paragraph:**

As shown in FIG. 12, the SiO<sub>2</sub> layer 440 is etched using the Invar® (FeNi36) 400 having the electron control hole 420 as a mask so that the electron control hold 420 can be a through hole.